Title: Gas Assisted Etching and Material Deposition on micro- and nano-scale

Training duration: 3 days

Training cost: Groups of 1 – 3 trainees, US$3600 per group

Background required: Basic FIB operator training, basic background in physics, chemistry, or material science

Student Objective: Understanding basics of GAE and material deposition, influence of beam raster parameters on etching and deposition processes, Ga implantation, specifics of in-via milling and deposition

Equipment: Micrion 2000, 2500, 9000, 9100, 986, 986FC, Vectra 986(+), VectraVision, any FIB or FEB equipment

Syllabus: TBD, available online by June 30, 2004